•	Application No.	Applicant(s)
Notice of Allowability	09/671,538	MAZUMDER ET AL.
	Examiner	Art Unit
	Chad Rapp	2125
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to the amendment filed on 03/23/04.		
2. The allowed claim(s) is/are <u>1-20</u> .		
3. The drawings filed on <u>27 September 2000</u> are accepted by the Examiner.		
<ul> <li>4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some* c) None of the: <ol> <li>Certified copies of the priority documents have been received.</li> <li>Certified copies of the priority documents have been received in Application No.</li> <li>Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).</li> </ol> </li> <li>* Certified copies not received:</li> </ul>		
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		
5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached		
1) hereto or 2) to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t		
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT		
Attachment(s)  1. ☐ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🔲 Interview Summar	Patent Application (PTO-152) y (PTO-413),
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0	Paper No./Mail Da 08), 7. ☐ Examiner's Amend	dree  Iment/Comment
Paper No./Mail Date  4.   Examiner's Comment Regarding Requirement for Deposit	8. 🛛 Examiner's Statem	nent of Reasons for Allowance
of Biological Material	9. Other	

Application/Control Number: 09/671,538

Art Unit: 2125

## **REASONS FOR ALLOWANCE**

1. The following is an examiner's statement of reasons for allowance:

As to independent claim 1, "creating a data base including acceptable direct metal deposition process parameters based upon previously obtained empirical data", in combination with the other claimed elements and features is not taught nor fairly suggested by the prior art of record.

As to independent claim 11"a database including acceptable direct metal deposition process parameters based upon previously obtained empirical data" in combination with the other claimed elements and features is not taught nor fairly suggested by the prior art of record.

## 2. Prior art

Coronel et al. discloses a semiconductor fabrication process. The patent describes a database but it is a database that contains wafer recipes not direct metal deposition process parameters.

Mccay et al. discloses a laser alloying process which is a different process than Coronel et al. The Mccay et al. invention does not teach a direct metal deposition process parameters database.

In addition the other elements of the independent claims use the database of the present invention to determine acceptable parameters. Even though the prior uses its database to check the wafer process, it does not teach containing information in the form of acceptable parameters of direct metal deposition process.

3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue

Application/Control Number: 09/671,538

Page 3

Art Unit: 2125

fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for

Allowance."

Conclusion

4. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Chad Rapp whose telephone number is (571)272-3752. The

examiner can normally be reached on Mon-Fri 11:00-7:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Leo Picard can be reached on (571)272-3749. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

L-P.P.

Cnad Kapp Evaminer

Art Unit 2125

cjr

LEO PICARD
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2100